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**Attorney Docket No.: NECW 18.159** 

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Inventor

: Atsushi NISHIZAWA

Serial No.

: 09/751,979

Filed

: December 29, 2000

Title

: MANUFACTURING METHOD OF SEMICONDUCTOR

INTEGRATED CIRCUIT INCLUDING SIMULTANEOUS

FORMATION OF VIA HOLE REACHING METAL WIRING AND

CONCAVE GROOVE IN INTERLAYER FILM AND

SEMICONDUCTOR INTEGRATED CIRCUIT MANUFACTURED

WITH THE MANUFACTURING METHOD

Examiner

: George A. Goudreau

Group Art Unit

: 1763

Commissioner for Patents P. O. Box 1450 Alexandria, VA 22313-1450

## PETITION FOR EXTENSION OF TIME

SIR:

Applicant requests that the time for taking action in this case be extended pursuant to 37 CFR 1.136(a) for:

[X] one month

[] three months

[] two months

09751979

[] four months

The fee set in 37 CFR 1.17 for the extension of time is \$110.00

06/27/2003 ZJUHARI 00000009 501290

110.00 DA 01 FC:1251

[] Fee enclosed. Please charge any additional fee required for this extension of time to Deposit Account No. 50-1290. A duplicate copy of this paper is enclosed.			
[X] Charge fee to Deposit Account No. 50-1290. A duplicate copy of this paper is enclosed.			
	[] Applicant is a small entity entitled to pay reduced fees in this application. A ified small entity statement:		
[	] has been filed	[] is enclosed	
A	Also enclosed is a:		
[	X] Response to Official Action ] Notice of Appeal	[] Appeal Brief	
		Respectfully submitted,	

What If p

Michael I. Markowitz Reg. No. 30,659

KATTEN MUCHIN ZAVIS ROSENMAN 575 Madison Avenue New York, New York 10022-2585 (212) 940-8687

Docket No.: NECW 18.159